Amendments to the Abstract

Please <u>replace</u> the abstract of the disclosure with the following new abstract of the disclosure:

In a method for crystallization or dopant activation heat treatment of a semiconductor film upon a thermally susceptible non-conducting substrate lying onto a susceptor, an induction coil is installed in close proximity of the semiconductor film and disposed so that the electrical current direction is aligned parallel to the in-plane direction of the semiconductor film, and an alternating electrical current is introduced in the induction coil to generate an alternating magnetic field through the semiconductor film heated by the susceptor to the extent that the semiconductor film can be induction-heated.